

NASA SBIR Success Story:- Active Edge-Control in Polishing of Mirror Segments and Other Applications

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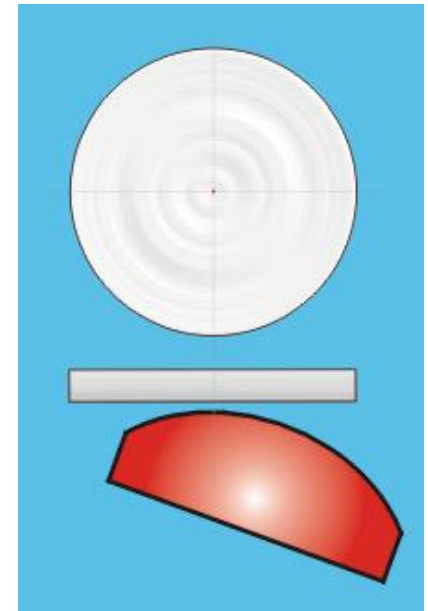
ZEEKO^{Ltd}

This talk

- Starting-point – NASA SBIR grant
- E-ELT and prototype segments
- Another application of edge-control
- Acknowledgements

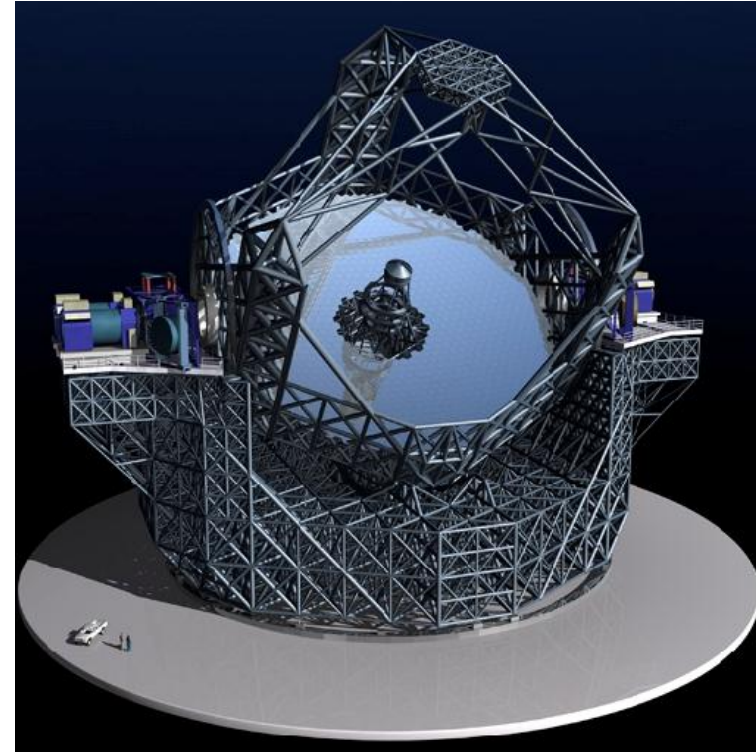
NASA SBIR grant

- “Edge Control in Large Segmented Optics Using Zeeko Polishing Technology”, Proposal S4.04-9574
- Demonstrated the basic method
 - Compressible spherical bonnet
 - Rotated and axis precessed
 - Tool compressed against the part
 - Delivers variable spot-size



The 39.3m aperture European Extremely Large Telescope

- Segmented primary mirror
 - 798 hexagonal segments +133 spares
 - Each 1.4m a/corners
 - Irregular hexagons
 - 50mm thick
 - ~ 200 microns max asphericity



Prototype segments near edge of primary. Reflect the earlier 42m telescope design with 84m ROC segments.

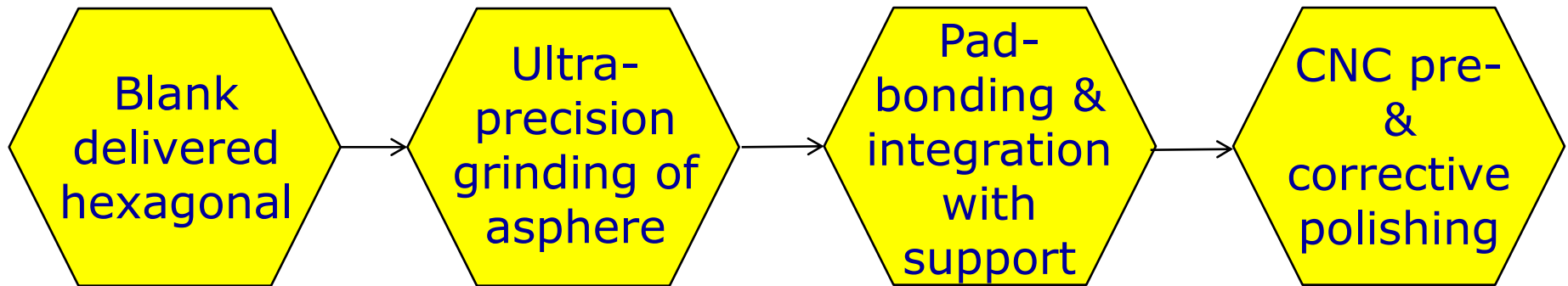
Segment production-rate & quality

- Construction schedule:- 2-3 segments per week
- Segment warping harness in the telescope will remove most of the low-order aberrations

ESO specification (abridged!)	Average	Maximum
RMS surface form (excluding 10mm edge-zone)	25nm	50nm
RMS surface form (ESO Zernike allowances removed)	7.5nm	15nm
PVq (95%) edge mis-figure (surface) in edge-zone	100nm	200nm

- RMS surface form *includes* errors in *matching* segment base-radii and conic-constants

Process-chain and metrology



In-situ metrology

National Facility for Ultra Precision Surfaces

Hosted by OpTIC in North Wales
Operated by Glyndŵr University



Zeeko IRP1600
under test-tower
On-axis optical test

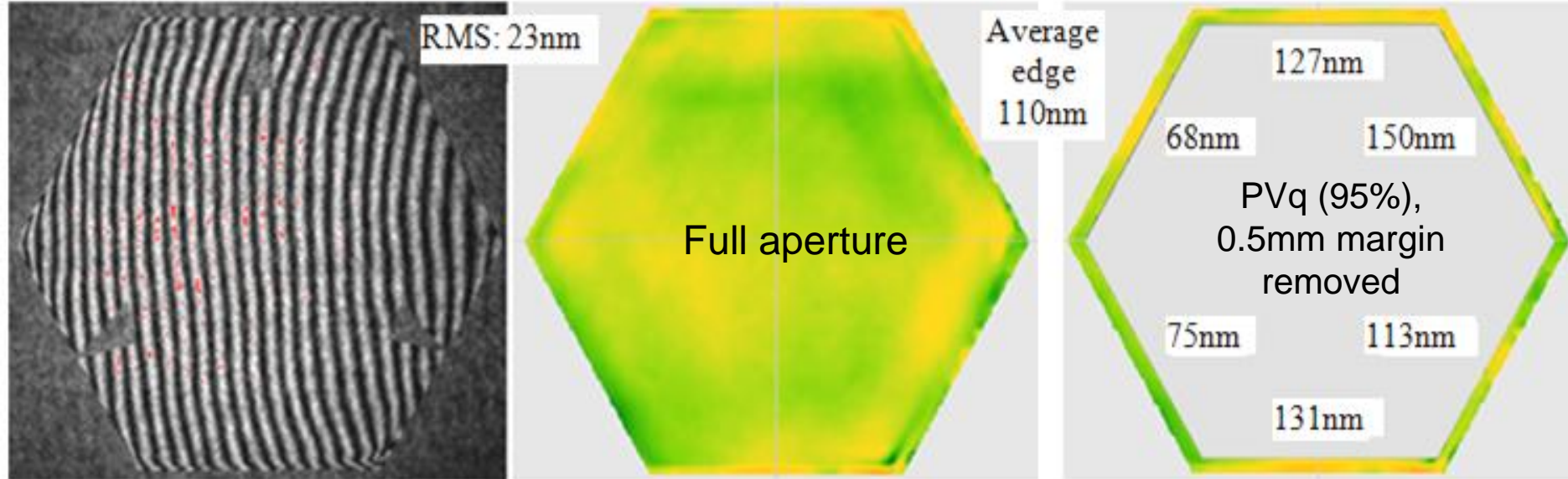


On-machine
deployment of
pentaprism
profilometer

Edge-polishing strategy

1. CNC-grind the off-axis asphere
2. Apply 0.5mm of the final 1mm bevel
3. Bonnet polishing programmed to leave turned-up edge at every stage
4. Up-turn progressively narrowed and lowered
5. Hard pitch tool to remove residual up-stand
6. Final 0.5mm bevel applied at end

Repeated edge-trials on 400mm borosilicate spherical parts



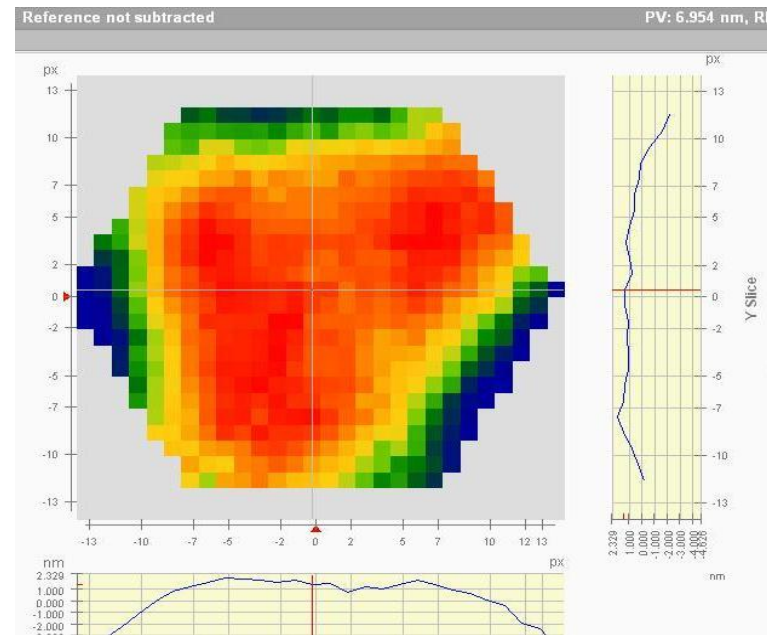
In 10mm wide edge zone (to start of bevel):-

110nm PVq surface edge-misfigure (average over 6 edges)

Grinding 1st aspheric segment SPN01 (Zerodur)



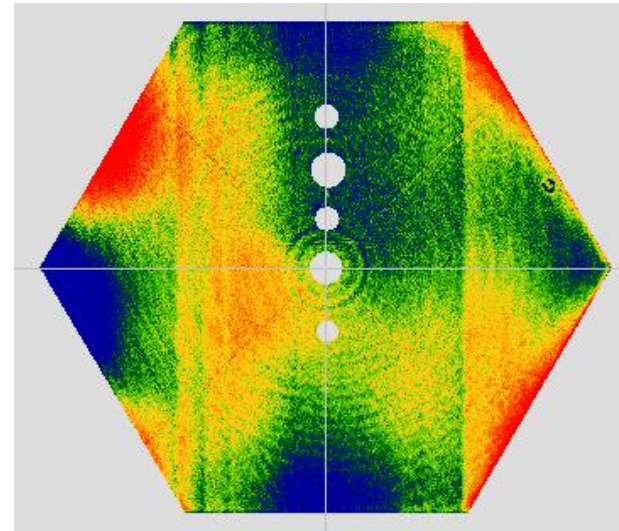
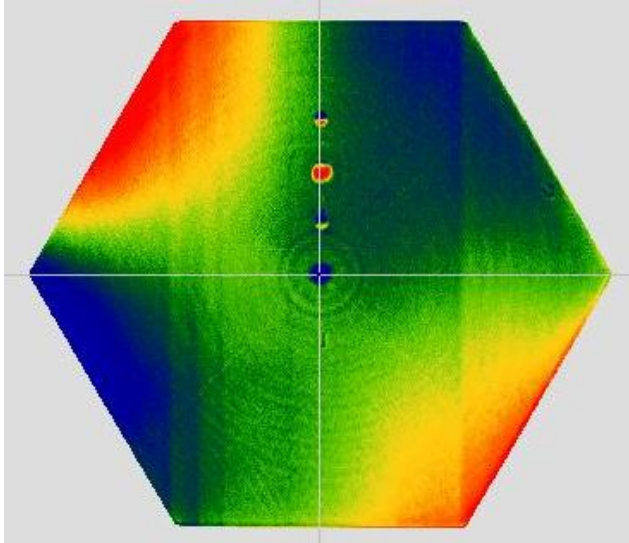
- Cranfield University BoXTM m/c
- Built by Cranfield Precision Ltd
 - **6.5 μ m PV** measured on grinding platen (Cranfield Univ. CMM)
 - **~ 150nm** mid-spatials



CMM data on 50mm grid, by
courtesy Cranfield University

Zeeko polishing SPN01

- Used extensively for equipment / process / metrology / software de-bugging and qualification

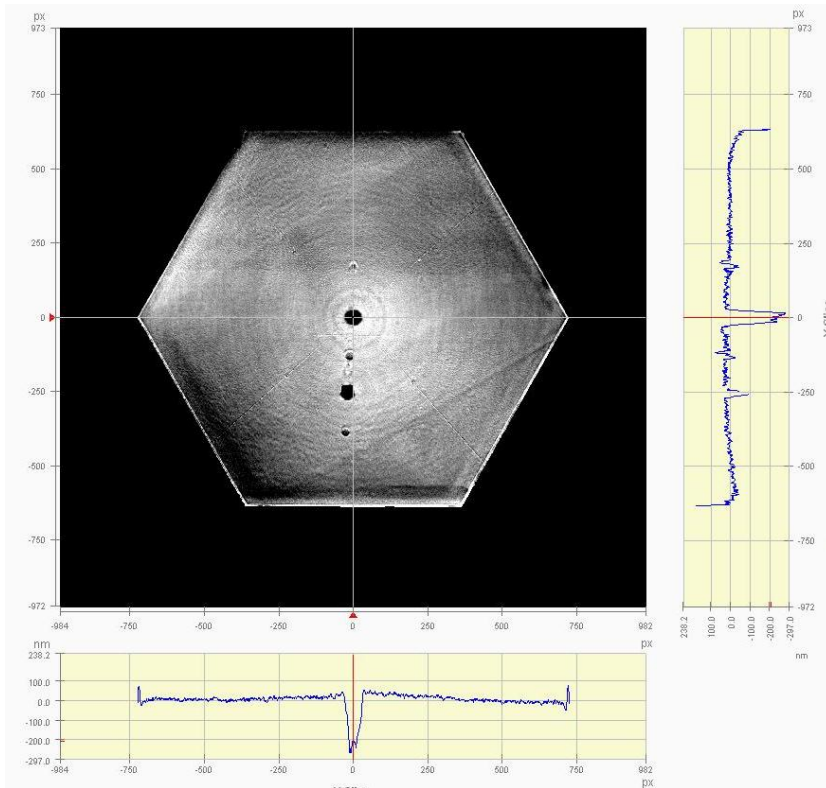


- SPN01 then held, due to Test Tower thermal issues
- Now rectified:- stable to $\sim \pm 0.25$ degs C

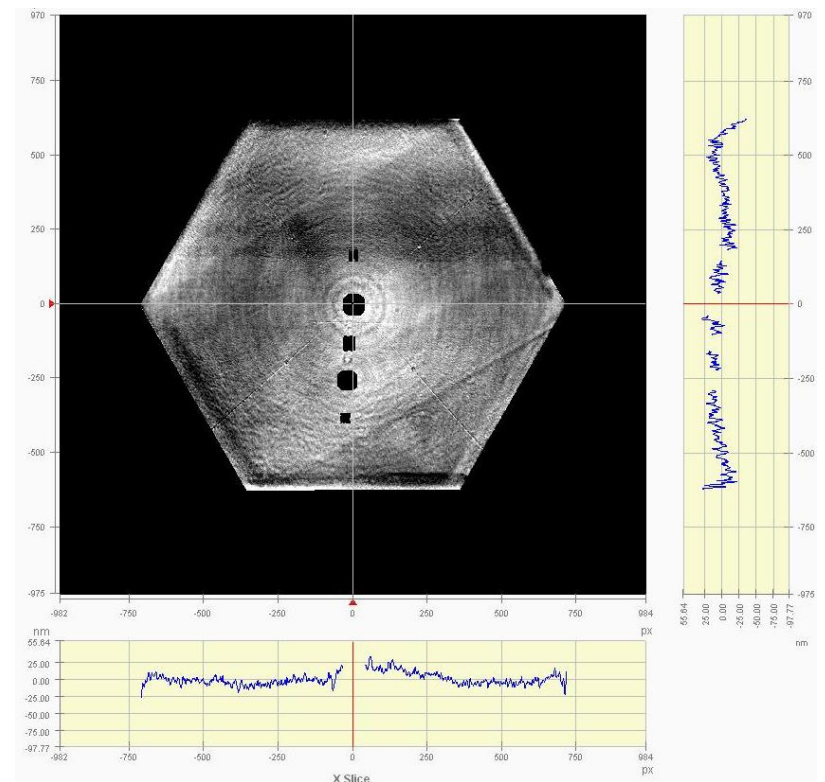
BoX grinding SPN04 Corning ULE

- Again, mounted on diamond-turned platen
- After grinding, $\sim 2\mu\text{m}$ “flash pre-polish”
 - Measured on **27 point hydrostatic** support
 - Grinding form-error **> 40 μm PV** (4X expected)
 - grinding support ?
 - springing due to “Twyman effect” ?
- Needed to remove $> 60\mu\text{m}$ DC material in polishing and retain quality of edges.

SPN04 under acceptance ... this week!

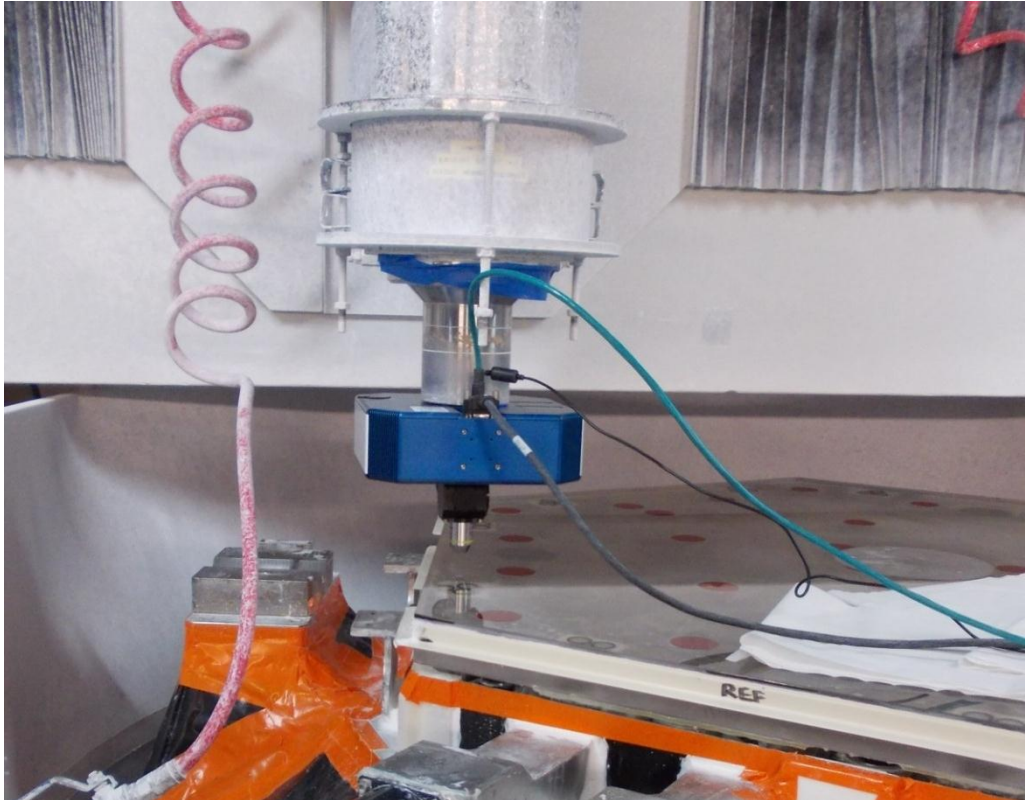


Full Aperture to edge
Only tip/tilt removed
22.9nm RMS Surface



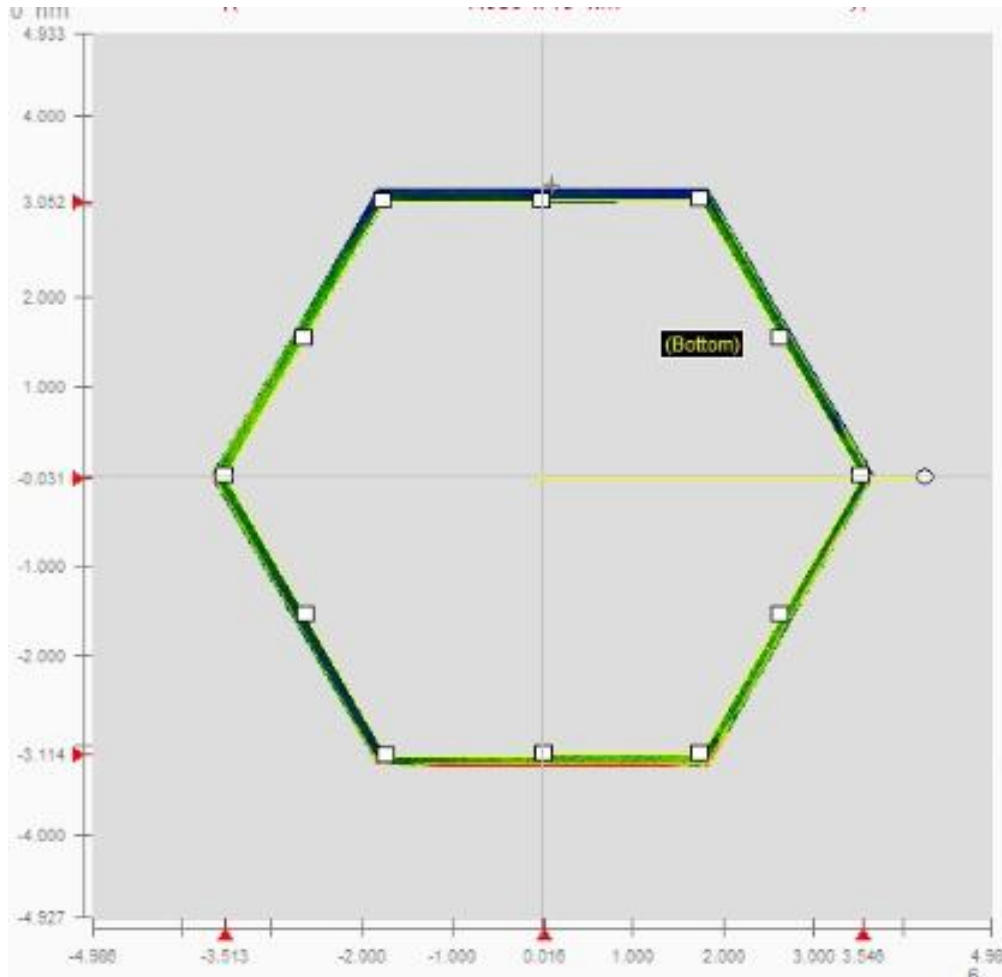
10mm edge zone cropped
ESO low-order allowances removed
CGH artifacts masked
10.3nm RMS Surface

3D Surface-texture measurement



- 4D Technologies STA1 white-light interferometer
- Mounted in Zeeko machine tool-holder
- Automated for multiple sample-areas
- SPN04 – uniform texture
~1nm Sq

Edge result on SPN04



- Final 0.5mm of bevel still to be applied
- Phase-map cropped
 - Leaving 10mm wide edge-zone
 - Edges turned up
 - Average mis-figure over six edges is:-

172nm PVq (95%) surface

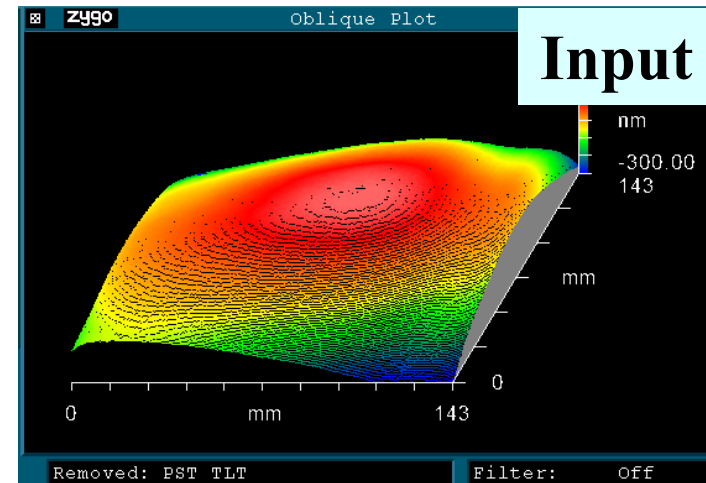
EUV photolithography photomasks

- Photomasks
 - Fused silica window + chrome pattern
 - One photomask needed for each layer in a wafer
- Next-generation EUV photomasks:-
 - 30-100nm PV form error
 - Edge dead-zone < 5mm wide
- With standard CMP on square blanks – tough!

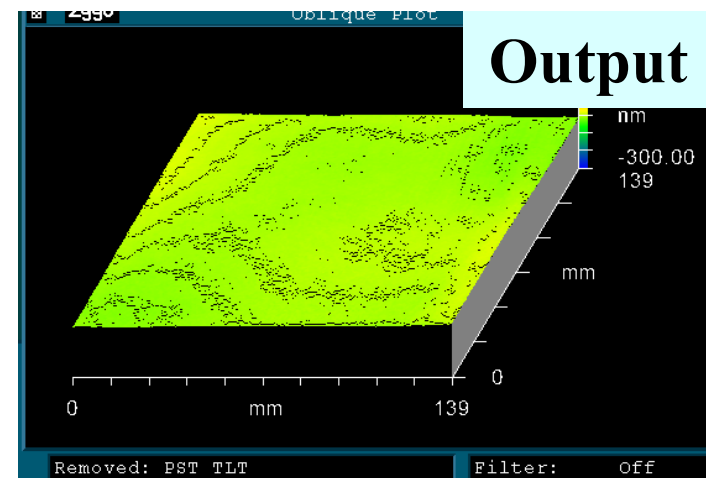
Photomasks



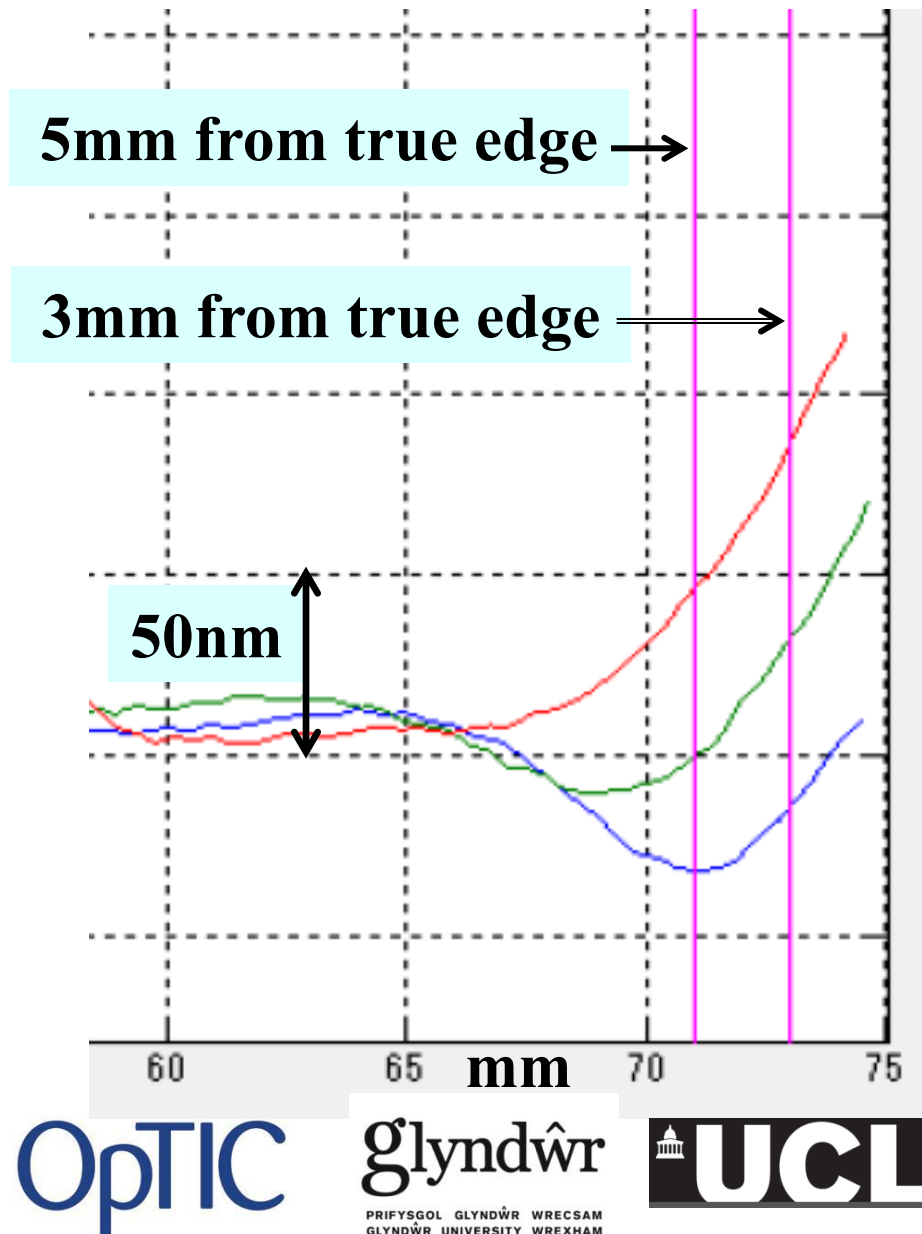
Photomask on Zeeko
IRP200 machine



Corrective polishing
within active area



Results of three edge-lift regimes on a photomask



- Zeeko bonnet polishing alone exceeds edge-spec.
- Overall surface in active area:-
 - Input **611 nm PV**
 - Output **42nm PV**
 - Texture **< 0.5nm**

Conclusions

- An end-to-end process chain
 - Part at final shape and size throughout
 - Well-suited to automated production-line
 - Edge control well understood
 - Applicable to various sectors ...from segmented telescopes to photomasks!
- Next – finish SPN01
- Then polish SPN03 (has been BoX-ground)

Thank you!

Acknowledgements

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- ESO: segment prototype contract
- Substantial financial support from:-
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 - Welsh Government:
- Zeeko Ltd: Build of IRP1600 machine and tech. support
- Cranfield University and Cranfield Precision Ltd: development of BoX grinder